

# Ultra-compact Silicon 90° Optical Hybrid by Adjoint-based Inverse Design Method

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**Abstract**—We demonstrate an ultra-compact 2×4 90° optical hybrid with adjoint-based inverse design method. The device footprint is 6.4 μm × 4.4 μm. For S and R-light input, the insertion losses are less than 0.78 dB.

**Keywords**—Inverse design; silicon photonics; 90° optical hybrid

## I. INTRODUCTION

In recent years, coherence optical communications are promising to be commercially applied in optical systems. 90° optical hybrid, as a key component in DSP-based optical demodulation in coherence modulation format such as the QPSK, has recently attracted considerable research attention [1].

However, the traditional 90° optical hybrid is based on the principle of multimode interference, and its size is typically on the order of server hundred micrometers [2].

The essence of on-chip optical device design is to search a geometric structure in the solution space to make the evaluation function meet the requirements under the constraints of Maxwell's equations and the material and size constraints. In recent years, as a new type of photonics design method, inverse design has achieved many devices with ultra-compact and high-efficiency characteristics [3, 4]. Through inverse design optimization, the designer can search the geometric structure in the solution space more deeply.

This paper uses the inverse design method to design an ultra-compact silicon 2×4 90° optical hybrid. The method is based on density material parameterization [5] and the adjoint method [6]. The device's footprint is 6.4 μm × 4.4 μm, and the insertion loss 0.78 dB for the S-light input and 0.76 dB for the R-light input.

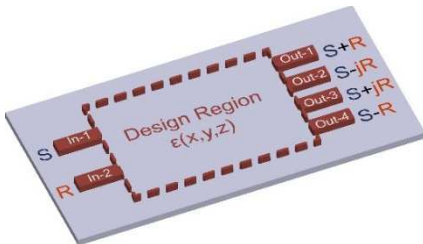


Fig.1. Function schematic diagram of the 2×4 90° optical hybrid.

## II. DEVICE DESIGN

We show the function of the 2×4 90° optical hybrid in Fig. 1. The device divides input S-light into four outputs equally, and the four output lights have the same phase. For R-light input, the device also divides the light intensity equally, but the phases of the output lights corresponding to the Out-1 ~ Out-4 are 0°, -90°, 90°, and 180°, respectively. The phase 0° is consistent with the output phase of S-light. We choose the platform a commercial silicon-on-insulator (SOI) wafer with 220 nm top silicon layer, 3 μm buried oxide layer and silicon dioxide cladding. The working wavelength is set to 1550 nm. The design task is to search for the distribution of the relative permittivity  $\epsilon$  in the design area in Fig. 1, so that the device can realize the functions mentioned above. We can use a mathematical optimization problem to describe the design problem,

$$\begin{aligned} \max FOM(E, H, \epsilon) \\ s.t. \quad g(E, H, \epsilon) = 0 \end{aligned} \quad (1)$$

where, FOM is the device's figure of merit, and  $g(E, H, \epsilon)$  is Maxwell's electromagnetic equations.

We choose the energy coupling efficiency of the input port and the output port as the FOM to evaluate the structures in this task. For the S-light input, the input mode is  $\begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_S$ , and

the target output mode is  $\begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_{out-1} + \begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_{out-2} + \begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_{out-3} + \begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_{out-4}_S$ . The corresponding mode coupling efficiency is FOM<sub>1</sub>. And for the

R-light input, the input mode  $\begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_R$ , and the corresponding

target output mode is  $\begin{bmatrix} TE_0 \\ 0^\circ \end{bmatrix}_{out-1} + \begin{bmatrix} TE_0 \\ -90^\circ \end{bmatrix}_{out-2} + \begin{bmatrix} TE_0 \\ 90^\circ \end{bmatrix}_{out-3} + \begin{bmatrix} TE_0 \\ 180^\circ \end{bmatrix}_{out-4}_R$ . We

define the energy coupling efficiency of the input and output modes as FOM<sub>2</sub>. Where TE<sub>0</sub> represents the mode order of the corresponding waveguide, and the angle is the relative phase value of different output ports. Then we let the total FOM<sub>Total</sub> = FOM<sub>1</sub> × FOM<sub>2</sub>.

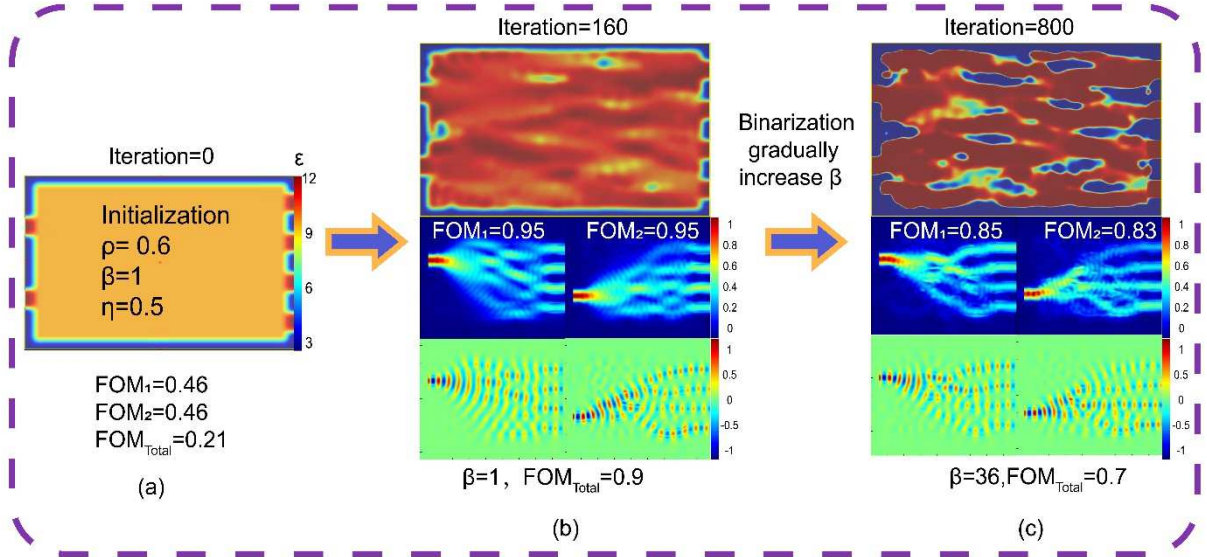


Fig.2. Device optimization process. (a) The initial structure and optimization parameters. (b) The optimization result obtained by retaining  $\beta = 1$ . (c) The device structure and FOM value when  $\beta = 36$ .

In the design strategy, to express the permittivity  $\epsilon(x,y,z)$ , we use density-based material parameterization. This method first introduces a normalized design variable  $\rho$ , and the final  $\epsilon$  value is obtained as follows,

$$\tilde{\rho}_i = \frac{\sum_{j \in N_i} \omega(\mathbf{x}_j) \rho_j}{\sum_{j \in N_i} \omega(\mathbf{x}_j)}, \quad \omega(\mathbf{x}_j) = R - |\mathbf{x}_i - \mathbf{x}_j|, \quad (2)$$

$$\bar{\rho}_i = \frac{\tanh(\beta \cdot \eta) + \tanh(\beta \cdot (\tilde{\rho}_i - \eta))}{\tanh(\beta \cdot \eta) + \tanh(\beta \cdot (1 - \eta))}, \quad (3)$$

$$\epsilon_i = \epsilon_{\min} + (\epsilon_{\max} - \epsilon_{\min}) \bar{\rho}_i. \quad (4)$$

In Eq. (2),  $\omega(\mathbf{x}_j)$  is the two-dimensional linear hat-shape filter [5]. The  $\beta$  in Eq. (3) is the projection parameter that controls the intensity of the projection. In the optimization process, we gradually increasing the value of  $\beta$  to make  $\bar{\rho}_i$  gradually tend to 0 or 1.

To determine how to modify the value of the design parameter  $\rho_i$ , according to adjoint method, we use forward simulation and adjoint simulation to calculate the gradient  $dFOM/d\epsilon(x,y,z)$ . Then, use the chain rule of derivative to get the gradient of FOM respect to the design variable  $dFOM/d\rho_i$ . Based on the gradient, we update the design variable  $\rho_i$  with the method of moving asymptotes (MMA) [7].

We use MATLAB code to implement the optimization strategy and use Lumerical FDTD solutions to simulate the electromagnetic field. MATLAB processes the field data and performs the iteration.

### III. DESIGN PROCESS AND RESULT

#### A. Optimization Process

We show the device optimization process in Fig. 2. First, as shown in Fig. 2(a), we set the initial design variable  $\rho = 0.6$ . We keep the parameter  $\beta = 1$  unchanged in the first stage. In this case,  $\epsilon_i$  in the design region can take any value in  $[\epsilon_{SiO_2}, \epsilon_{Si}]$ , which is conducive to the algorithm to search for higher performance structures. After 160 iterations, the device structure is shown in Fig. (b). The corresponding FOM value is  $FOM_{Total} = 0.9$ ,  $FOM_1 = 0.95$ ,  $FOM_2 = 0.95$ . Fig. (b) shows the simulated electric field distribution of the input S and R-

light field at the In-1 port and In-2 port. It is worth noticing that the device's performance, at this time, is the optimal value in the entire optimization process. However, this structure cannot be implemented to on-chip manufacturing due to its permittivity having many intermediate values  $[\epsilon_{SiO_2}, \epsilon_{Si}]$ . Then we perform the binarization stage. In this stage, we still use the MMA algorithm to iterate the  $\rho_i$  but gradually increase the value of  $\beta$ . In Fig. (c), we show an intermediate result in the binarization process. The iteration is 800 and  $\beta$  is 36. As shown in figure, the area with intermediate value is reduced, and most of the area has been binarized. Meanwhile, the FOM value also decreased, and  $FOM_{Total}$  is about 0.7. We show the simulated electric field distribution in Fig. 2(c).

#### B. Result

Finally, we terminate the algorithm terminates at 1600 iterations, and the  $\beta$  value is 128. We cut off the  $\rho$  value and set the  $\rho_i$  greater than 0.5 to 1 and the  $\rho$  less than 0.5 to 0. The final layout of the device is shown in Fig. 3. The device footprint is  $6.4 \mu m \times 4.4 \mu m$ . All input and output waveguides are  $0.5 \mu m$  width. The gap between the two input waveguides is  $1.5 \mu m$ , and the output waveguides gaps are  $0.6 \mu m$ . The structure of the device is complex, irregular and non-intuitive. These complex structures affect light waves at the micro-nano level, which reduces the device's size to achieve ultra-compactness.

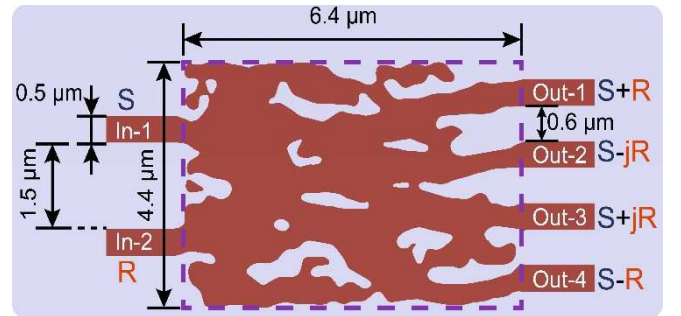


Fig.3. Schematic diagram of optimized device layout.

Fig. 4 shows the simulation results of the device. The FDTD simulation wavelength is 1550 nm, and the simulation mesh is 20nm. Fig. 4(a) is a schematic diagram of the field

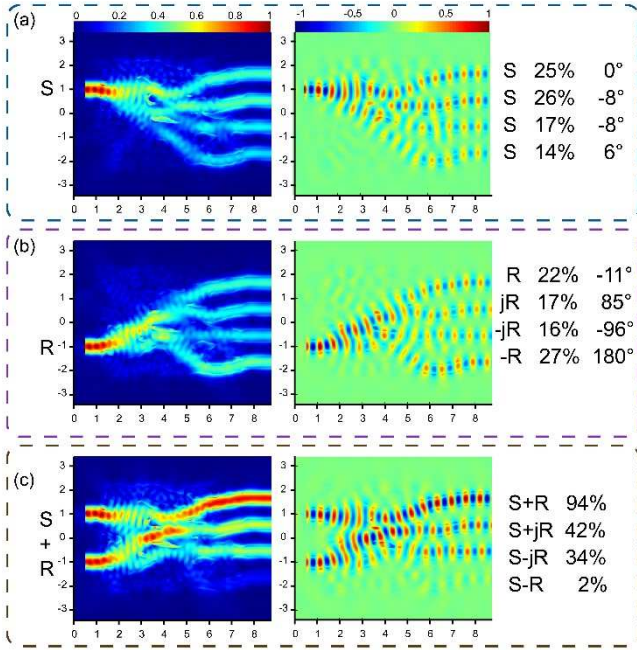


Fig.4. Simulation results of the device. (A) The simulated electric field magnitude and  $E_y$  component corresponding to S-light input. (B) The magnitude and  $E_y$  component corresponding to R-light input. (C) The simulated electric field intensity and  $E_y$  component corresponding to S and R-light input.

intensity and  $E_y$  component distribution of the S-light input from the In-1 port. The device divides the S-light into four channels. We use the phase of Out-1 port as the reference phase, which is defined as  $0^\circ$ . The intensity and phase corresponding to the four output ports are (25%,  $0^\circ$ ), (26%,  $-8^\circ$ ), (17%,  $-8^\circ$ ) and (14%,  $6^\circ$ ). Fig. 4(b) shows the corresponding electric field intensity and  $E_y$  component when R light is input from In-2 port. Similarly, we still use the phase of the S-Out1 light as the reference phase. At this time, the four outputs corresponding to the R light are (22%,  $-11^\circ$ ),

(17%,  $85^\circ$ ), (16%,  $-96^\circ$ ) and (27%,  $180^\circ$ ). Fig. 4(c) shows the device's electric field intensity and  $E_y$  response when S and R light are input together with the same phase. In this case, the total input light intensity is 2, and the output light intensity of the Si four channels is 94%, 42%, 34%, and 2%, respectively.

#### IV. CONCLUSION

In conclusion, using the inverse design method, we designed an ultra-compact silicon  $2 \times 4$   $90^\circ$  optical hybrid. The device footprint is  $6.4 \mu\text{m} \times 4.4 \mu\text{m}$ . The simulation results show that the insertion loss of the device for the S-light input is 0.78 dB, and the phase deviations of the four ports do not exceed  $8^\circ$ . For the R-light input, the insertion loss of the device is less than 0.76 dB, and the phase deviations are less than  $11^\circ$ .

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